

6[New]. A dry etching method as claimed in Claim 5, wherein the compound containing hydrogen is one or more members selected from the group consisting of ammonia, hydrocarbon, and hydrogen sulfide.

A2 7[New]. A dry etching method as claimed in Claim 5, wherein a mask material selected from the group consisting of titanium and a titanium alloy covers the metallic surface on etching.

8[New]. A dry etching method as claimed in Claim 6, wherein a mask material selected from the group consisting of titanium and a titanium alloy covers the metallic surface on etching.